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Patent
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT



) Group Art Unit: 1756

) Examiner: S. Mohamedulla

AMENDMENT UNDER 37 C.F.R. §1.116

Assistant Commissioner for Patents
Washington, D.C. 20231

Date: March 2, 2001

Sir:

This amendment responds to the Office Action dated December 5, 2000

(Paper No. 6). Please amend the above-noted application as follows:

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TC 1700 MAIL ROOM

IN THE CLAIMS:

Please replace claims 7 and 28 as follows:

7. (Twice Amended) A photomask comprising:

a transparent substrate;

a hollow section formed on a surface of said transparent substrate;

a shade pattern made up of a shade film, said shade film formed in said hollow section; and

a phase shift pattern formed by etching said transparent substrate including said shade pattern formed in said hollow section.

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